

Synthesis of CuO Wires from Layered Organic-Inorganic Hybrids

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Copper oxide (CuO) is a narrow band-gap semiconducting oxide that has been widely studied in electrochemical cells, in photothermal and photoconductive materials, and as a heterogeneous catalyst.¹⁻³ Various techniques have been used to fabricate CuO nanostructures.³⁻⁶ One-dimensional (1D) CuO can be obtained through thermal treatment by using the precursors Cu(OH)₂ or Cu₂(OH)₂CO₃ as a sacrificial template.⁷⁻⁹ Layered organic-inorganic hybrids are characterized by strong intralayer covalent or ionic bonding in an inorganic frame, and weak interlayer interactions such as van der Waals forces between organic molecules.¹⁰⁻¹⁴ Most layered organic-inorganic hybrid materials fabricated to date were obtained by intercalation of organic molecules into the inorganic layer. In this work, we report the preparation of CuO from the layered organic-inorganic hybrid, Cu₂(OH)₃(C₁₂H₂₅SO₄). CuO wires are formed by a self-aggregation of nanoparticles. The morphologies of the aggregated CuO products are analyzed using scanning electron microscopy and transmission electron microscopy.

Experimental Section

The layered organic-inorganic compound Cu₂(OH)₃-(C₁₂H₂₅SO₄) was prepared by slow titration of a mixed solution containing 100 mL of Cu(NO₃)₂·2.5H₂O (8.6 mmol), 100 mL of C₁₂H₂₅SO₄Na (4.3 mmol), and 100 mL of NaOH (13.0 mmol). The resulting precipitate was aged at room temperature for 7 days. The products were filtered, washed with water to remove unreacted sodium dodecyl-sulfate and impurities, and dried under vacuum at room temperature. CHN elementary analysis was used to confirm the product. Anal. calcd. (found) for C₁₂H₂₈O₇SCu₂: C, 32.5 (32.4), H, 6.4 (6.7), N; 0.0 (0.0). The CuO was synthesized by thermal decomposition of Cu₂(OH)₃(C₁₂H₂₅SO₄) at 850 °C for 1 h.

The structures of Cu₂(OH)₃(C₁₂H₂₅SO₄) and CuO were analyzed by powder X-ray diffraction (XRD, Phillips PW 1710) using Cu K α radiation. The morphology of the CuO was characterized by scanning electron microscopy (SEM, Phillips XL30 ESEM-FEG) and transmission electron microscopy (TEM, Jeol 2010). The thermal behavior of the precursor was studied by thermogravimetric analysis (TGA, Seiko Exstar 6000).

Results and Discussion

The copper hydroxide salts, Cu₂(OH)₃X (X = exchange-

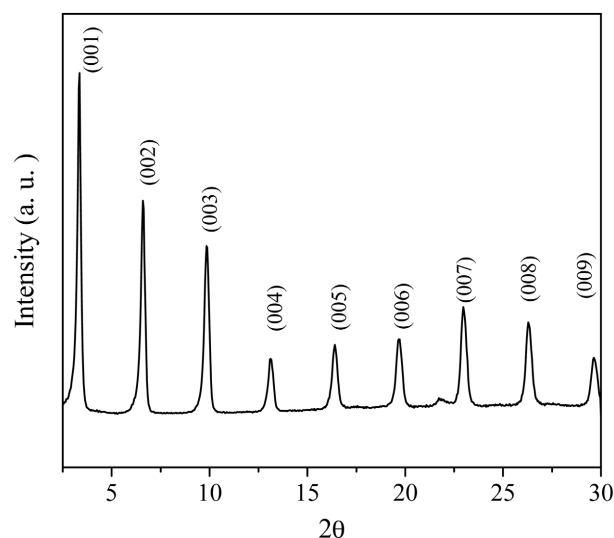


Figure 1. X-ray diffraction pattern and Miller indices of Cu₂(OH)₃(C₁₂H₂₅SO₄).

able anion, NO₃⁻, RCOO⁻, etc.), show a botallackite-type structure, in which two distinct copper atoms lie in 4 + 2 (oxygen + X) and 4 + 1 + 1 (oxygen + oxygen + X) environments.^{15,16} The anion is located in the interlayer, while the molecular component coordinates the copper ion. The copper hydroxide salts form plate-like structures. The interlayer distance depends on the intercalated organic moiety. Figure 1 shows the X-ray diffraction pattern and Miller indices of Cu₂(OH)₃(C₁₂H₂₅SO₄). The series of (00*l*) peaks at regular intervals indicates a typical layered structure. The basal spacing is calculated to be 26.2 Å, which is equal to that reported by Rabu *et al.*^{17,18} The interdigitated monolayer structure of the dodecylsulfate is oriented normal to the [Cu₂(OH)₃]⁺ layer.

Figure 2 shows a typical TGA curve for the Cu₂(OH)₃-(C₁₂H₂₅SO₄) precursor in an atmospheric flow. The curve shows four pronounced weight loss steps. The first weight loss at 45 °C is due to the dehydration of water adsorbed within the precursor, where the actual empirical formula for the precursor is Cu₂(OH)₃(C₁₂H₂₅SO₄)·0.38H₂O. Between 180 °C and 250 °C, there is a major weight loss due to the decomposition of intercalated dodecylsulfate where the suggested product is the stable CuO·CuSO₄.¹⁹ The calculated and measured weight losses are 46.9% and 48.6%, respectively. The third weight loss is observed in the temperature range of 250-410 °C. In this temperature range,

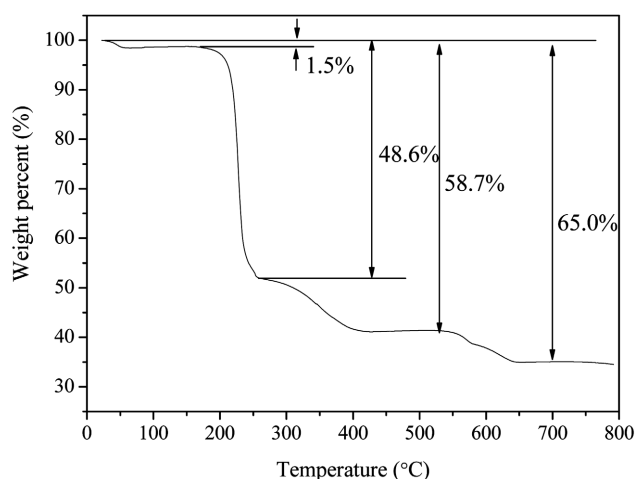


Figure 2. TGA curve of $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$.

$\text{CuO} \cdot \text{CuSO}_4$ is partially decomposed to form the more stable $1.5\text{CuO} \cdot 0.5\text{CuSO}_4$ with calculated and measured weight losses of 59.3% and 58.7%, respectively.¹⁹ Above 650 °C, the $1.5\text{CuO} \cdot 0.5\text{CuSO}_4$ decomposes to form 2CuO with calculated and measured weight losses of 64.6% and 65.0%, respectively. The possible chemical reactions for the thermal decomposition of $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4) \cdot 0.38\text{H}_2\text{O}$ are presented below:

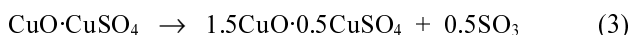
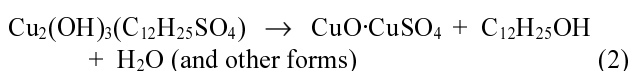
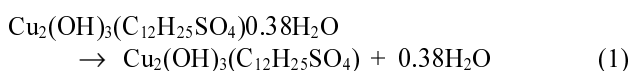


Figure 3 shows the X-ray diffraction pattern and Miller indices of CuO obtained by the thermal decomposition of $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4) \cdot 0.38\text{H}_2\text{O}$ at 850 °C for 1 h. The diffraction peaks correspond to pure CuO with a monoclinic

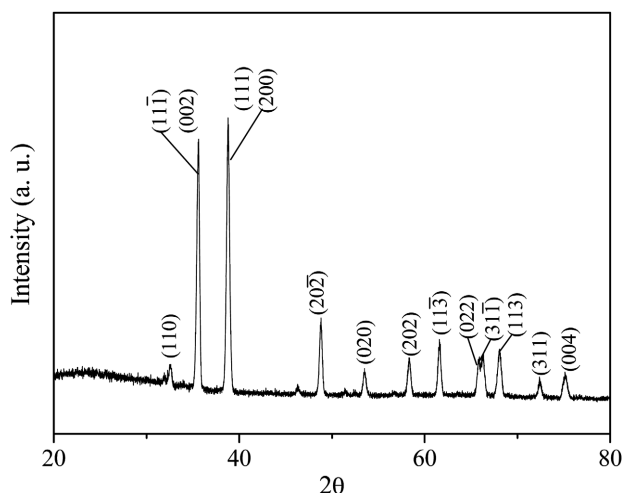


Figure 3. X-ray diffraction pattern and Miller indices of CuO.

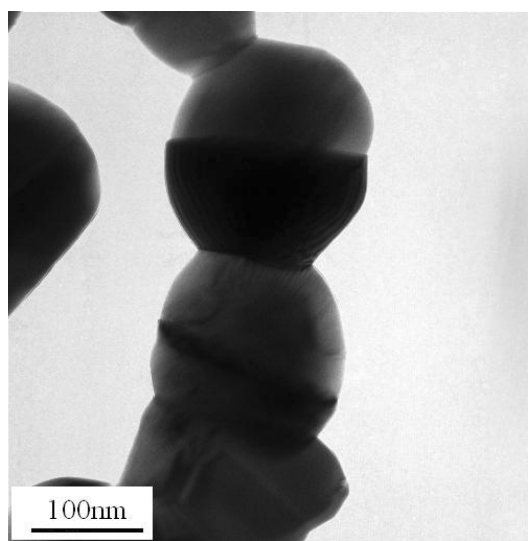


Figure 4. TEM image of CuO product obtained from the $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$ precursor by thermal treatment at 850 °C.

structure ($a = 4.6837 \text{ \AA}$, $b = 3.4226 \text{ \AA}$, $c = 5.1288$, $\beta = 99.54^\circ$, JCPDS 45-0937).²⁰ The XRD peaks exhibit no broadening since the particles are much larger than the nanometer range.

Figure 4 shows the TEM images of the CuO product obtained by thermal decomposition of the $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$ precursor at 850 °C. The image consists of a large number of particles with a fairly uniform diameter of 150 nm. Figure 5(A) shows the SEM morphology of the wire-like structure of the resulting CuO product. SEM examination shows that the CuO wires are $\sim 1 \mu\text{m}$ thick with lengths up to 20 μm . Note that there are no flat or spherical structures. As can be seen from Figure 5(B), the CuO wire consists of particles with sizes on the order of a few hundred nanometers. The SEM image reveals that the micron-sized CuO wire is in fact an assembly of dozens of hundred nanometer-sized particles. Therefore, the CuO nanoparticles aggregate and assemble to form micron-sized CuO wires. If the aggregation and assembly of CuO particles were random, a spherical CuO product would result.

The $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$ precursor has a typical layered structure with a basal spacing of 26.2 Å. The $\text{CuO} \cdot \text{CuSO}_4$ product is formed by thermal decomposition of the organic dodecyl sulfate in the $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$ precursor at 200 °C. Since the interlayer distance is relative long, the layered precursor structure slowly collapses to form $\text{CuO} \cdot \text{CuSO}_4$ at this temperature, with the $\text{CuO} \cdot \text{CuSO}_4$ particles stacked layer by layer. At higher temperature, the $\text{CuO} \cdot \text{CuSO}_4$ compounds finally decompose to form CuO particles. These CuO particles aggregate in a specific way to form micron-sized CuO wire. The formation mechanism of the micron-sized CuO wire is not clear. However, the formation of aggregated CuO wires depends on the morphology of the precursor. The decomposition of the layered $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_{25}\text{SO}_4)$ leads the CuO particles to integrate and to form wire-like CuO. The micron-sized CuO wires are

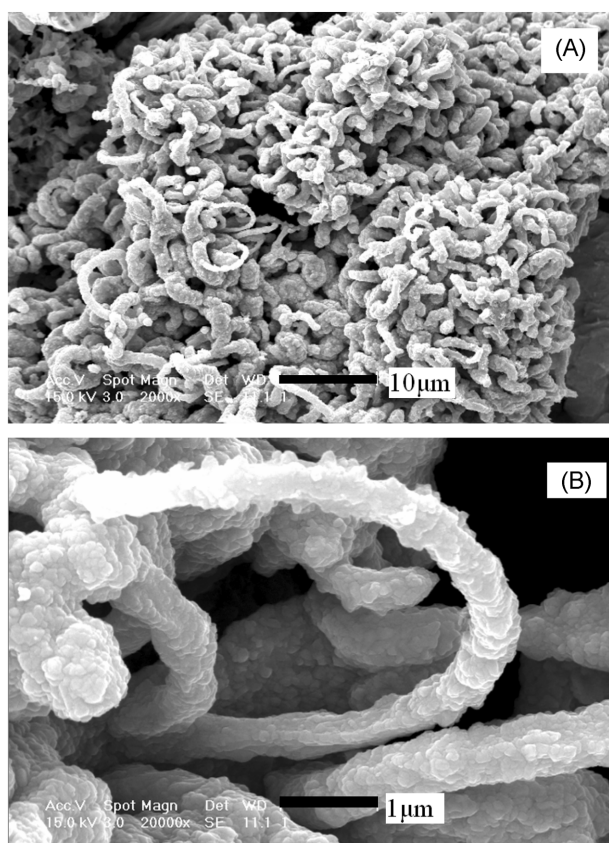


Figure 5. SEM images of CuO wire obtained from the $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_2\text{SO}_4)$ precursor by thermal treatment at 850 °C; (A) $\times 2000$ and (B) $\times 20000$.

synthesized from two-dimensional (2D) $\text{Cu}_2(\text{OH})_3(\text{C}_{12}\text{H}_2\text{SO}_4)$ by simple thermal decomposition in the absence of a suitable template.

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